10/043065

<u>IN THE UNITED STATES PATENT AND TRADEMARK OFFICE</u>

TOANS Applicant:

Leonard Forbes

Examiner:

Kiesha L Rose

Serial No.:

10/043,065

Group Art Unit:

2822

Filed:

January 09, 2002

Docket:

303.684US3

Title:

P-CHANNEL DYNAMIC FLASH MEMORY CELLS WITH ULTRATHIN

TUNNEL OXIDES

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

In compliance with the duty imposed by 37 C.F.R. § 1.56, and in accordance with 37 C.F.R. §§ 1.97 et. seq., the enclosed materials are brought to the attention of the Examiner for consideration in connection with the above-identified patent application. Applicant respectfully requests that this Information Disclosure Statement be entered and the documents listed on the attached Form 1449 be considered by the Examiner and made of record. Pursuant to the provisions of MPEP 609, Applicant requests that a copy of the 1449 form, initialed as being considered by the Examiner, be returned to the Applicant with the next official communication.

Pursuant to 37 C.F.R. §1.97(b), it is believed that no fee or statement is required with the Information Disclosure Statement. However, if an Office Action on the merits has been mailed, the Commissioner is hereby authorized to charge the required fees to Deposit Account No. 19-0743 in order to have this Information Disclosure Statement considered.

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The Examiner is invited to contact the Applicant's Representative at the below-listed telephone number if there are any questions regarding this communication.

Respectfully submitted,

LEONARD FORBES

By his Representatives,

SCHWEGMAN, LUNDBERG, WOESSNER & KLUTH, P.A. P.O. Box 2938

Minneapolis, MN 55402

(612) 371-2157

Date 15- MARCH 2004

David R. Cochran

Reg. No. 46,632

Name

Signatur

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Substitute for form 1449APTO	Under the Paperwork Reduction Act of 1999, no persons are required to respons to a collection of information unless it contains a valid OMS control number. Complete if Known		
INFORMATION DISCLOSURE STATEMENT BY APPLICANT	Application Numb r	10/043065	
(Use as many sheets as not ensery)	Filing Date	January 9, 2002	
	First Named Inv ntor	Forbes, Leonard	
	Gr up Art Unit	2822	
MAR 1 7 2004 (5)	Examiner Name	Rose, Kiesha	
Sheet 1 of 2	Attorney Docket No: 3	03.684US3	

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INFORMATION DISCLOSURE	Application Number	10/043065		
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MAR	Examiner Name	Rose, Kiesha		
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